

EAS1 - [dell.wsp.1]

File Edit View Look Window Help

Pending Active

- L1: (31) resistance adj detector adj element
- L2: (195) (magnetS and ("300" adj nm)) and interferoS
- L3: (53585) resistance and element
- L4: (5026) 3 and magnetic
- L5: (89) 4 and height
- L6: (0) 5 and interferoS
- L7: (0) 5 and interferS
- L8: (0) 2 and height
- L9: (0) 2 and magnetoresists
- L10: (3065) magnetoresistS
- L11: (7) 10 and lapping
- L12: (4056) magnetoresistS
- L13: (388) 12 and lapping
- L14: (10) 13 and interferomets
- L15: (8) ("4423450" | "4613913" | "4859501" | "4949207"
- L16: (0) 2001014617.UREN.
- L17: (9823) resistive adj element
- L18: (1235) 17 and height
- L19: (154) 18 and interferens
- L20: (0) 18 and inteferoS
- L21: (28; 18 and interferoS
- L22: (176) 19 or 21
- L23: (3) 22 and (lapped or lapping)
- L24: (40; nakata and toshihiko
- L25: (7) 24 and magnets
- L26: (3697) "240" adj nm
- L27: (137) 26 and (magnetic adj head)
- L28: (56; 27 and height

Bailed

DBs: USPAT

Default operator: OR

27 and height

BRK form A Break Form Image Text HTML

	U	I	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Retrieval C	Inventor
1	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 6421123 B1	20020716	46	Position detecting apparatus	356/399	356/400; 356/401		Shiraishi, Naom
2	<input type="checkbox"/>	<input type="checkbox"/>	US 6417922 B1	20020709	18	Alignment device and lithographic apparatus	356/401	250/548; 356/400		Dirksen, Peter
3	<input type="checkbox"/>	<input type="checkbox"/>	US 6414744 B1	20020702	11	Mask handling apparatus for lithographic projection	355/75	355/76; 414/935;		Kuiper, Doede e
4	<input type="checkbox"/>	<input type="checkbox"/>	US 6414743 B1	20020702	73	Exposure apparatus, exposure	355/69	355/30;		Nishi, Kenji et

Ready NUM